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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/711,793	10/06/2004	Irene Chen	UTEP0015USA	5792
27765	7590	11/30/2006		EXAMINER
NORTH AMERICA INTELLECTUAL PROPERTY CORPORATION P.O. BOX 506 MERRIFIELD, VA 22116			MCPHERSON, JOHN A	
			ART UNIT	PAPER NUMBER
			1756	

DATE MAILED: 11/30/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

<b>Office Action Summary</b>	<b>Application No.</b>	<b>Applicant(s)</b>	
	10/711,793	CHEN ET AL.	
	<b>Examiner</b>	<b>Art Unit</b>	
	John A. McPherson	1756	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --  
**Period for Reply**

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

**Status**

1) Responsive to communication(s) filed on 06 October 2004.  
 2a) This action is **FINAL**.                    2b) This action is non-final.  
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

**Disposition of Claims**

4) Claim(s) 1-14 is/are pending in the application.  
 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.  
 5) Claim(s) \_\_\_\_\_ is/are allowed.  
 6) Claim(s) 1,2,9-11,13 and 14 is/are rejected.  
 7) Claim(s) 3-8 and 12 is/are objected to.  
 8) Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

**Application Papers**

9) The specification is objected to by the Examiner.  
 10) The drawing(s) filed on 04 October 2006 is/are: a) accepted or b) objected to by the Examiner.  
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

**Priority under 35 U.S.C. § 119**

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  
 a) All    b) Some \* c) None of:  
 1. Certified copies of the priority documents have been received.  
 2. Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.  
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

**Attachment(s)**

1) Notice of References Cited (PTO-892)  
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  
 3) Information Disclosure Statement(s) (PTO/SB/08)  
 Paper No(s)/Mail Date \_\_\_\_\_

4) Interview Summary (PTO-413)  
 Paper No(s)/Mail Date. \_\_\_\_\_

5) Notice of Informal Patent Application  
 6) Other: \_\_\_\_\_

## DETAILED ACTION

### ***Claim Rejections - 35 USC § 102***

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1, 2, 9-11, 13 and 14 are rejected under 35 U.S.C. 102(b) as being anticipated by JP 7-323428 (JP '428). JP '428 discloses a process of making a stamper for the manufacture of a photo-sheet required for a liquid crystal display as a back light comprising the steps of applying a photoresist solution to a base (corresponding to a preferred surface treatment process of the present invention, see claim 9), placing a photomask on the resist layer, irradiating the resist layer, developing the resist layer, heating the resist layer to a temperature which carries out a heat flow to form a pattern of convex microlenses, forming a metal layer on the microlenses, and exfoliating the base and resist layer from the metal layer. See the abstracts, paragraphs [0013]-[0021] of the computer-generated translation, and Figures 1(a)-(i).

2. Claims 1, 2, 9-11, 13 and 14 are rejected under 35 U.S.C. 102(b) as being anticipated by Applicant's description of the prior art in the specification. Applicant

discusses a conventional method for forming a light guide plate insert mold comprising the steps of providing a substrate, performing a priming process by coating a HMDS layer onto the substrate to convert the surface condition of the substrate (i.e. a surface treating process), coating a photo resist layer (i.e. a preferred surface treating process of the present invention, see claim 9), exposing and developing to form a plurality of photo resist patterns, and performing a flow process so that each photoresist pattern is given a smooth microlens surface. See [Para 4]-[Para 7] of the present specification.

3. Claims 1, 2, 9-11, 13 and 14 are rejected under 35 U.S.C. 102(e) as being anticipated by US 2005/0037290 (US '290). US '290 discloses a method for manufacturing a light guide plate stamper comprising the steps of providing a substrate, applying an adhesion promoting agent of the silane series on the substrate (i.e. a surface treating process), coating a photo-resist onto the substrate (i.e. a preferred surface treating process of the present invention, see claim 9), exposing and developing the photo-resist film to form micro patterns, heating and melting the developed photo-resist film, depositing a metal film, and stripping off and removing the residual patterns and the substrate to form the stamper. See the abstract, paragraphs [0017]-[0025], and Figures 1-8.

4. Claims 1, 2, 9-11, 13 and 14 are rejected under 35 U.S.C. 102(e) as being anticipated by US 2006/0028952 (US '952). US '952 discloses a method of fabricating

a molding core for a light guide plate comprising the steps of providing a substrate, baking the substrate in a vacuum or in a nitrogen atmosphere to dehydrate the substrate (i.e. a surface treatment process), coating a photo-resist on the substrate (i.e. a preferred surface treating process of the present invention, see claim 9), exposing and developing the photo-resist film to form a photo-resist pattern, heating the substrate so that the photo-resist pattern starts to melt, forming a nickel film on the substrate, and separating the nickel film from the substrate and photo-resist pattern. See the abstract, paragraphs [0023]-[0027], and Figures 1-6.

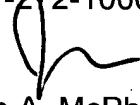
***Allowable Subject Matter***

5. Claims 3-8 and 12 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
  
6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to John A. McPherson whose telephone number is (571) 272-1386. The examiner can normally be reached on Monday through Friday, 8:00 AM to 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Art Unit: 1756

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.



John A. McPherson  
Primary Examiner  
Art Unit 1756

JAM  
11/22/06